

IN THE SPECIFICATION:

Please amend paragraph [0045] to read:

-- The less the plasma density utilized at the provided deposition surfaces, relative to the maximum plasma density ~~migrating around~~ in beam axes A, the more homogeneous, i.e. equally distributed, becomes the plasma density distribution. But that simultaneously at only approximately 20% of the plasma density utilization nevertheless very high deposition rates of at least 400 nm/min at temperatures of maximally 500 °C can be attained, is surprising. --